



# Trimethyltin fluoride: A new fluorinating reagent for the preparation of silicon fluorides <sup>1</sup>

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#### Abstract

A new fluorinating reagent for the preparation of silicon fluorides is described. The preparation of  $Me_2SiF_2$ ,  $(CH_2=CH)MeSiF_3$ ,  $EtSiF_3$ ,  $CH_2=CHSiF_3$ , n-PrSiF<sub>3</sub>, n-PrSiF<sub>3</sub>, n-HexSiF<sub>3</sub>(Hex =  $C_6H_{13}$ ) and PhSiF<sub>3</sub> using  $Me_3SnF$  is reported. The products are formed in high yield. The resulting  $Me_3SnCl$  can be easily recovered and again converted to the fluorinating reagent.

Keywords: Fluorinating reagent; Silicon fluorides: Recycling

#### 1. Introduction

Silicon fluorides are a well established class of compounds and numerous reviews can be found in the literature. A most recent compilation appeared in the Gmelin handbook containing SiF compounds and their appropriate references [1,2]. Recently, we reported in a short note on the preparation of SiF<sub>4</sub> and Me<sub>3</sub>SiF using Me<sub>3</sub>SnF 1 as a fluorinating reagent [3]. An almost quantitative conversion was observed. Moreover, Me<sub>3</sub>SnF turned out to be an efficient reagent for the preparation of organometallic fluorides [4]. Herein, we report on the preparation of several di- and trifluorides of silicon.

# Table 1 Numbering scheme, yields, and physical data of compounds 2–8

Reactant	Product	Compound no.	Yield (%)	hp (°C)	MS (EI)	$^{19}$ F NMR $\delta(C_6D_6)$ ppm"	J(F-Si) (Hz)
Me <sub>2</sub> SiCl <sub>2</sub>	Me <sub>2</sub> SiF <sub>2</sub> [8]	2	97	2	96	32.55	289.6
$(CH_2=CH)MeSiCl_2$	$(CH_2=CH)MeSiF_2$	3	97	24	108	25.93	286.7
EtSiCl <sub>3</sub>	EtSiF <sub>3</sub> [9]	4	96	<b>-4</b>	114	22.27	283.7
CH <sub>2</sub> =CHSiCl <sub>3</sub>	CH <sub>2</sub> =CHSiF <sub>3</sub> [10]	5	94	-10	112	20.35	263.2
n-PrSiCl <sub>3</sub>	n-PrSiF <sub>3</sub> [1,2,9]	6	94	25	128	24.86	285.0
ı-HexSiCl <sub>3</sub>	n-HexSiF <sub>3</sub> [1,2]	7	88	92	170	25.59	286.0
PhSiCl <sub>3</sub>	PhSiF <sub>3</sub> [1,2,11]	8	86	101	162	21.85	268.0

<sup>&</sup>lt;sup>a</sup>External standard C<sub>6</sub>F<sub>6</sub>.

#### 2. Results and discussion

Me<sub>3</sub>SnF (1) has been known since 1918 [5–7] and has a polymeric structure containing Sn–F–Sn intermolecular bonds. It is easily prepared from the corresponding chloride using NaF in aqueous solution. Prior to use 1 should be thoroughly dried in vacuo. Otherwise oxofluorides are formed as by-products in the reaction mixture.

The difluorides Me<sub>2</sub>SiF<sub>2</sub> (**2**) and (CH<sub>2</sub>=CH)MeSiF<sub>2</sub> (**3**) have been prepared without using any solvents. The products are recovered by trap-to-trap distillation. The yields are almost quantitative (see Table 1). The trifluorides EtSiF<sub>3</sub> (**4**), CH<sub>2</sub>=CHSiF<sub>3</sub> (**5**), *n*-PrSiF<sub>3</sub> (**6**), *n*-HexSiF<sub>3</sub> (**7**) and PhSiF<sub>3</sub> (**8**) are formed in high yields using the corresponding chlorides and Me<sub>3</sub>SnF in a molar ratio of 1:3. The nonoptimized yields vary between 86% and 96%. Only in the case of

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<sup>&</sup>lt;sup>1</sup> Dedicated to Professor K. Kühlein on the occasion of his 60th birthday.

PhSiF<sub>3</sub> was a small amount of nonvolatile solvent added for a smooth reaction.

The compounds have been characterized by EI (electron ionisation) mass spectroscopy and  $^{19}\mathrm{F}$  NMR spectroscopy. Compounds **2–8** exhibit their molecular ions as the highest mass peak (see Table 1). The  $^{19}\mathrm{F}$  NMR chemical shifts are in the range of 20–32 ppm using  $C_6F_6$  as an external standard.

These few experiments demonstrate that almost all organometallic halides of silicon may be converted to the corresponding fluorides using Me<sub>3</sub>SnF or any other R<sub>3</sub>SnF compound as a fluorinating reagent.

## 3. Experimental section

All experiments were performed under a dry nitrogen atmosphere using a glass reactor equipped with a Teflon valve. Me<sub>3</sub>SnF was synthesized by published methods [5–7] and sublimed at 100°C/10<sup>-4</sup> mbar prior to use. The organometallic silicon chlorides were obtained from Aldrich, ABCR, Fluka and Janssen Chimica.

 $^{19}\mathrm{F}$  NMR spectra were recorded by means of a Bruker AM 250 instrument using TMS and  $C_6F_6$  as external standards. Mass spectroscopic analyses were performed with a Finnigan MAT 8230 instrument. IR spectra were recorded in the gas phase using a BIO-RAD FTS-7 instrument.

### 4. Preparations

Me<sub>2</sub>SiF<sub>2</sub> (**2**): 3.84 g (21 mmol) Me<sub>3</sub>SnF were placed in a 30-ml reactor. After evacuation of the reactor on a vacuum line, 1.29 g (10 mmol) of Me<sub>2</sub>SiCl<sub>2</sub> were condensed onto the Me<sub>3</sub>SnF under cooling with liquid nitrogen. The reactor was slowly warmed to room temperature, kept at this temperature for 30 min, and the resulting product **2** purified by trap-to-trap distillation. Yield 0.9 g (97%). IR 2984, 1273, 947, 913, 827, 816, 331 cm<sup>-1</sup>.

 $(CH_2=CH)MeSiF_2$ : (3) 3.84 g (21 mmol) Me<sub>3</sub>SnF and 1.41 g (10 mmol)  $(CH_2=CH)MeSiCl_2$  were reacted as described for **2**. Yield 1.05 g (97%) of **3**. IR 2985, 1604, 1415, 1276, 1015, 935, 888, 811, 629, 403, 318 cm<sup>-1</sup>.

EtSiF<sub>3</sub> (4): 5.7 g (31 mmol) of Me<sub>3</sub>SnF were reacted with 1.64 g (10 mmol) of EtSiCl<sub>3</sub> to yield 1.1 g (96%) of 4. IR 2985, 1265, 993, 955, 890, 877, 420, 389, 355 cm<sup>-1</sup>.

 $CH_2$ = $CHSiF_3$  (5): 5.7 g (31 mmol)  $Me_3SnF$  and 1.61 g (10 mmol)  $CH_2$ = $CHSiCl_3$  were reacted to yield 1.05 g

(94%) of **5**. IR 2985, 1610, 1420, 1006, 958, 880, 542, 424, 359 cm<sup>-1</sup>.

n-PrSiF<sub>3</sub> (**6**): To 5.7 g (31 mmol) Me<sub>3</sub>SnF were added 1.77 g (10 mmol) n-PrSiCl<sub>3</sub> using a syringe. 1.2 g (94%) of **6** were obtained after distillation. IR 2973, 1468, 1227, 1069, 1021, 947, 905, 872, 439, 367, 330 cm<sup>-1</sup>.

*n*-HexSiF<sub>3</sub> (7): 5.7 g (31 mmol) of Me<sub>3</sub>SnF were placed in a 30-ml reactor cooled with liquid nitrogen under an atmosphere of dry nitrogen and finally 2.2 g (10 mmol) of *n*-HexSiCl<sub>3</sub> were added using a syringe. The reactor is closed and slowly warmed to 50°C, and kept at this temperature for 30 min. After cooling to room temperature and trap-to-trap distillation, 1.5 g (88%) of 7 were obtained. IR 2971, 2940, 1199, 1029, 971, 890, 734, 481, 428, 389 cm<sup>-+</sup>.

PhSiF<sub>3</sub> (**8**): 5.7 g (31 mmol) of Me<sub>3</sub>SnF and methylnaphthalin (5 ml) were placed in a reactor, which was then cooled with liquid nitrogen, and 2.11 g (10 mmol) of PhSiCl<sub>3</sub> were added. 1.4 g (86%) of **8** were obtained after trap-to-trap distillation. IR 3083, 1598, 1434, 1140, 949, 854, 784, 741, 696 cm<sup>-1</sup>.

Recycling of Me<sub>3</sub>SnF: After removal of the products the residue containing Me<sub>3</sub>SnCl and a small amount of Me<sub>3</sub>SnF is treated with water. Me<sub>3</sub>SnF is not dissolved and separated by filtration. The resulting solution is treated with excess of a 15% solution of KF. Immediately Me<sub>3</sub>SnF precipitates and is recovered by filtration and washed three times with water. Both quantities of Me<sub>3</sub>SnF are combined, dried and finally sublimed in vacuo.

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